

KRAMER LEVIN NAFTALIS & FRANKEL LLP

919 Third Avenue

New York NY 10022

(212) 715-9100

2004 JAN 28 P 3:45

Fax Department: (212) 715-9191

Fax Number: (212) 715-9508

FROM: Gregor N. Neff
PHONE: (212) 715-9202

DATE: January 28, 2004

PLEASE DELIVER AS SOON AS POSSIBLE TO:

RECIPIENT	COMPANY	FAX NO.	PHONE NO.
1. Examiner Jilia M. Mohandesi Group Art 3728	U.S. Patent and Trademark Office	703 746 4248	

Total number of pages including this page: 6

The documents accompanying this facsimile transmission are intended only for the use of the addressee and may contain information that is privileged and confidential. If you are not the intended recipient, you are hereby notified that any dissemination of the communication is strictly prohibited. If you have received this communication in error, please notify us immediately by telephone. Thank you.

Re: U.S. Serial No. 09/879,613

URGENT ATTENTION - GROUP 3728- EXAMINER Jilia M. Mohandesi

Please see attached.

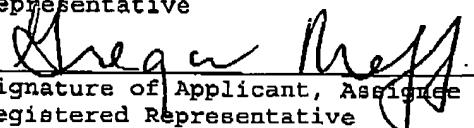
31013

PATENT
33168-2130IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : John Skoufis
Serial No. : 09/879,613
Filed : 06/12/2001
For : PEROXIDE PRESERVATION
Group Art Unit : 3728
Examiner : Mohandesi, Jilia M.

919 Third Avenue
New York, NY 10022

I hereby certify that this correspondence
is being facsimile transmitted to the
United States Patent Office, addressed to:
Examiner Mohandesi, Jilia M.
Group Art Unit 3728 -
Facsimile No. 703 746 4248
on January 28, 2004
Gregor N. Neff - Reg. No. 20,596
Name of Applicant, Assignee or Registered
Representative


Signature of Applicant, Assignee or
Registered Representative

LETTER

Dear Examiner Mohandesi:

As requested in our telephone discussion earlier today,
enclosed is a copy of the pending claims with the newly proposed
amendments.

31013

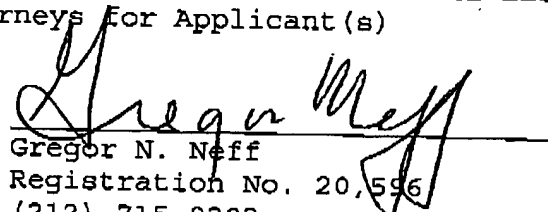
PATENT
33168-2130

I look forward to a telephone interview with you tomorrow morning at 9:00 A.M.

Respectfully submitted,

KRAMER LEVIN NAFTALIS & FRANKEL LLP
Attorneys For Applicant(s)

By:


Gregor N. Neff
Registration No. 20,596
(212) 715-9202

31013

PATENT
33168-2130IN THE CLAIMS:

Claim 1 (currently amended)

1. A method of packaging a PVA sponge for use in scrubbing semiconductor wafers, said method comprising:

- (a) placing said sponge in a container;
- (b) said sponge containing a quantity of de-ionized water with around 0.05% to less than 1% by volume of hydrogen peroxide; and
- (c) sealing said container.

Claim 2 (original)

2. A method as in Claim 1 in which said container is a flexible plastic bag made of a material resistant to deterioration due to contact with hydrogen peroxide, preferably polyethylene.

Claim 3 (currently amended)

3. A method as in Claim 1 in which said quantity of de-ionized water with hydrogen peroxide is between an amount sufficient to wet said sponge and an amount necessary to saturate said sponge.

Claim 4 (currently amended)

4. A method as in Claim 1 in which the volume of hydrogen peroxide is around 0.1%.

K13:2316822.1

31013

PATENT
33168-2130

Claim 5 (currently amended)

A method of packaging a cleaning article, said method comprising placing said cleaning article in a container, said cleaning article containing a quantity of de-ionized water, said water containing hydrogen peroxide in an amount effective to kill and retard the growth of bacteria in said cleaning article but less than an amount sufficient to develop significant quantities of metallic ions in said container, and sealing said container, in which said amount of hydrogen peroxide is about 0.05 to less than 1% by volume.

Claim 6 (original)

A method as in Claim 5 in which said cleaning article is a PVA sponge brush.

Claim 7 (original)

A method as in Claim 5 in which said cleaning article is a clean room wiper.

Claim 8 (withdrawn)

Claim 9 (currently amended)

A packaged cleaning article for use in clean rooms, said cleaning article having particulate, metal ion and anionic counts at or below the values specified for a clean room, said package comprising a sealed container, said cleaning article being positioned in said container, and containing a quantity of

KLJ:2316822.1

31013

PATENT
33168-2130

de-ionized water, said de-ionized water containing hydrogen peroxide in a concentration effective to kill and retard the growth of bacteria in said cleaning article, said amount being low enough to substantially ensure decomposition of said hydrogen peroxide in a relatively short period of time after the container is sealed and being below about 1% by volume in concentration.

Claim 10 (withdrawn)

Claim 11 (currently amended)

11. A cleaning article as in Claim 9 in which said concentration of hydrogen peroxide in said de-ionized water with hydrogen peroxide is between approximately 0.05% and less than 1%.

Claim 12 (currently amended)

12. A cleaning article as in Claim 9 in which said cleaning article is a PVA sponge for scrubbing semiconductor wafer surfaces, and said concentration of hydrogen peroxide is around 0.1 percent by volume.

Claim 13 (withdrawn)

Claim 14 (currently amended)

14. A cleaning article as in Claim 9 in which said container is a flexible plastic bag.

KL3:2316822.1